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FORM PTO-1390 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE (REV 10-2000) TRANSMITTAL LETTER TO THE UNITED STATES		ATTORNEY'S DOCKET NUMBER  MCW-002US
DESIGNATED/ELECTED OFFICE (DO/EO/US)		U.S. APPLACATION NO. AN MOVAN. 10: 30 CFR 1.5)
	NG UNDER 35 U.S.C.371	U.S. APP (C.5TION 18.910 % 9 34 CFR 1.5)
INTERNATIONAL APPLICATION PCT/GB00/00323	international filing date 07 February 2000 (07.02.00)	PRIORITY DATE CLAIMED 05 February 1999 (05.02.99)
TITLE OF INVENTION		
	TH MULTIPLE CORE LAYER	RS AND METHOD OF FABRICATION
THEREOF		
APPLICANT(S) FOR DO/EO/US  Paulo Vicente DA SILVA MA	RQUES et al.	
Applicant herewith submits to the United	States Designated/Elected Office (DO/EO/US	) the following items and other information:
1. 🗷 This is a FIRST submissio	n of items concerning a filing under 35 U	J.S.C.371.
2. This is a SECOND or SUI	BSEQUENT submission of items concern	ning a filing under 35 U.S.C. 371.
	to promptly begin national examination p	
<u> </u>	y the expiration of 19 months from the pi	
_	Application as filed (35 U.S.C. 371(c)(2	
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`	equired only if not communicated by the	international Bureau).
	ated by the International Bureau.	
	ne application was filed in the United Stat	
_ : " " " " " " " " " " " " " " " " " "	lation of the International Application as	
7. 🗷 Amendments to the claims	of the International Application under Po	CT Article 19 (35 U.S.C. 371(c)(3))
a. are attached hereto	(required only if not communicated by th	e International Bureau).
b.   have been commun	icated by the International Bureau.	
c. I have not been made	; however, the time limit for making such	n amendments has NOT expired.
; d. 🗷 have not been made	e and will not be made.	
8. An English language trans	lation of the amendments to the claims ur	nder PCT Article 19 (35 U.S.C. 371(c)(3)).
9. 🗷 An oath or declaration of t	he inventor(s) (35 U.S.C. 371(c)(4)). (ur	nexecuted) (4 Sheets);
<u></u>	lation of the annexes to the International	
PCT Article 36 (35 U.S.C. 37		
Items 11. to 16. below concern docu	ment(s) or information included:	
11. 🗷 An Information Disclosure	e Statement under 37 CFR 1.97 and 1.98	(2 sheets) with Form PTO-1449 (1 sheet);
12. An assignment document included	for recording. A separate cover sheet in o	compliance with 37 CFR 3.28 and 3.31 is
13. A FIRST preliminary ame (5 sheets));	ndment (7 sheets) (along with vers	ion of markings to show changes
☐ A SECOND or SUBSEQU	IENT preliminary amendment	
14. A substitute specification.		
15. A change of power of atto	rney and/or address letter.	
16. Other items or information: Transmittal Letter (2 sheets); PCT International Published Application (WO 00/46619) (with International Search Report) (38 sheets); International Preliminary Examination Report (18 sheets); Check in the amount of \$1530.00 (Filing Fee) based on large entity; Certificate of First Class Mailing (1 sheet); and Return Postcard.		
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U.S. APPLICATION NO. (if known, see 37 CFR 1.5) INTERNATIONAL APPLICATION NO. MCW-002US PCT/GB00/00323 CALCULATIONS PTO USE ONLY 17. Entry The following fees are submitted: BASIC NATIONAL FEE (37 CFR 1.492 (a) (1) - (5) ) .(a/o November 1, 2000): Neither international preliminary examination fee (37 CFR 1.482) nor international search fee (37 CFR 1.445(a)(2)) paid to USPTO and International Search Report not prepared by the EPO or JPO......\$1000 International preliminary examination fee (37 CFR 1.482) not paid to International preliminary examination fee (37 CFR 1.482) not paid to USPTO but international search fee (37 CFR 1.455(a)(2)) paid to USPTO ......\$710 International preliminary examination fee paid to USPTO (37 CFR 1.482) but all claims did not satisfy provisions of PCT Article 33(1)-(4).....\$690 International preliminary examination fee paid to USPTO (37 CFR 1.482) \$860.00 ENTER APPROPRIATE BASIC FEE AMOUNT = \$130.00 Surcharge of \$130.00 for furnishing the oath or declaration later than 20 months from the earliest claimed priority date (37 CFR 1.492(e)). CLAIMS NUMBER FILED NUMBER EXTRA **RATE** X \$18.00 \$540.00 Total claims **50-**20 = 30 X \$80.00 \$ Independent claims **2**-3 = 0 + 270.00 MULTIPLE DEPENDENT CLAIM(S) (if applicable) \$ \$1530.00 TOTAL OF ABOVE CALCULATIONS = Applicant claims small entity status. See 37 CFR 1.27. The fees indicated above are reduced by 1/2. SUBTOTAL Processing fee of \$130.00 for furnishing the English translation later than □ 20 □ 30 months from the earliest claimed priority date (37 CFR 1.492(f)). TOTAL NATIONAL FEE = Fee for recording the enclosed assignment (37 CFR 1.21(h)). The assignment must be \$ accompanied by an appropriate cover sheet (37 CFR 3.28, 3.31). \$40.00 per property TOTAL FEES ENCLOSED \$1530.00 \$ Amount to be: refunded charged a. Example Checks in the amount of \$ 1530.00 to cover the above fees are enclosed. ь. 🔲 in the amount of \$ to cover the above fees. Please charge my Deposit Account No. A duplicate copy of this sheet is enclosed. c. 🗷 The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment to Deposit Account No. 12-0080 . A duplicate copy of this sheet is enclosed. NOTE: Where an appropriate time limit under 37 CFR 1.494 op/1.495 has not been met, a petition to revive (37 CFR 1.137(a) or (b)) must be filed and granted to restore the application to pending status, SEND ALL CORRESPONDENCE TO: Anthony A. Laurentano, Esq. SIGNATURE Anthony A. Laurentano LAHIVE & COCKFIELD, LLP 28 State Street NAME Boston, Massachusetts 02109 38,220 **United States of America** REGISTRATION NUMBER (617)227-7400 Date: 03 August 2001

O9890694.O11002

JC09 Rec'd PCT/PTO 0 3 AUG 2001 09/890694

## IN THE UNITED STATES PATENT DESIGNATED OFFICE (DO/US) (National Phase of International App.: PCT/GB00/00323, W/O 00/46619)

In re the application of:

Paulo Vicente DA SILVA MARQUES et al.

International Application No.: PCT/GB00/00323

International Filing Date: 07 February 2000

U.S. Serial No.: Not Yet Assigned

Filed: Herewith

For: OPTICAL WAVEGUIDE WITH MULTIPLE

CORE LAYERS AND METHOD OF

FABRICATION THEREOF

Attorney Docket No.: MCW-002US

#### **BOX PCT**

Commissioner for Patents Washington, D.C. 20231

#### Certification Under 37 CFR 1.10

I hereby certify that the attached: Transmittal Letter (2 sheets); Preliminary Amendment (7 sheets (along with version of markings to show changes (5 sheets)); Unexecuted Declaration, Petition and Power of Attorney (4 sheets); PCT International Published Application (WO 00/46619) (with International Search Report) (38 sheets); International Preliminary Examination Report (18 sheets); Information Disclosure Statement (2 sheets); Form PTO-1449 (1 sheet); check in the amount of \$1530.00 (Filing Fee) based on large entity; Certificate of Express Mailing (1 sheet); and Return Postcard are being deposited by me with the United States Postal Service "Express Mail Post Office to Addressee" service, Mailing Label No. **EL 916 825 478 US**, under 37 CFR 1.10 on the date indicated below and is addressed to the Box PCT, Commissioner for Patents, Washington, D.C. 20231.

Date:	03 August 2001		
Name:	Vinny Cardoso	Signature: James	Central
		//	

# 09/890694

IN THE UNITED STATES PATENT DESIGNATED OFFICE (DO/US) (National Phase of International App.: PCT/GB00/00323, W/O 00/46619)

In re the application of:

Paulo Vicente DA SILVA MARQUES et al.

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Attorney Docket No.: MCW-002US

#### **BOX PCT**

Commissioner for Patents Washington, D.C. 20231

#### PRELIMINARY AMENDMENT

Dear Sir:

Preliminary to examination of the above-referenced patent application, please amend the enclosed above-titled International patent application as follows.

#### In the Claims

Please amend claims 4, 5, 8-11, 13, 14, 16, 17, 20-26, 28, 29, 33, 36, 39, 42, 50, 53, 55, 57, 58, 62, 65-67, 69-72, 77 and 78 as follows:

4. (Amended) A waveguide as claimed in claim 1, wherein the substrate comprises silicon and/or silica and/or sapphire.

- 5. (Amended) A waveguide as claimed in claim 1, wherein the substrate includes an intermediate layer-including a buffer layer formed on the substrate, wherein said buffer layer comprises a thermally oxidised layer of the substrate.
- 8. (Amended) A waveguide as claimed in Claim 5, wherein the intermediate layer further includes a lower cladding layer formed on said buffer layer.
- 9. (Amended) A waveguide as claimed in Claim 5, wherein the thickness of the buffer layer is in the range 5μm to 20μm.
- 10. (Amended) A waveguide as claimed in claim 1, wherein the second core layer is formed on the first core layer and said first core layer is formed on the substrate.
- 11. (Amended) A waveguide as claimed in Claim 1, wherein the first core layer is formed on the second core layer and said second core layer is formed on the substrate.
- 13. (Amended)A waveguide as claimed in claim 1, wherein the first core layer includes silica.
- 14. (Amended) A waveguide as claimed in claim 1, wherein the first core layer dopant includes dopant ions, including tin and/or cerium and/or sodium.
- 16. (Amended) A waveguide as claimed in claim 1, wherein the second core layer includes silica.
- 17. (Amended) A waveguide as claimed in claim 1, wherein the second core layer includes a phosphorus oxide.
- 20. (Amended) A waveguide as claimed in Claim 16, wherein the second core layer dopant includes a rare earth and/or a heavy metal and/or compounds of these elements.

- 21. (Amended) A waveguide as claimed in Claim 16 wherein the second core layer dopant includes rare earth is Erbium or Neodymium.
- 22. (Amended) A waveguide as claimed in claim 1, wherein the refractive indices of the first core layer and the second core layer are substantially equal.
- 23. (Amended) A waveguide as claimed in claim 1, wherein the refractive index of the waveguide core differs from that of the substrate by at least 0.05%.
- 24. (Amended) A waveguide as claimed in claim 1, wherein the thickness of the first core layer is in the range 0.2μm to 30μm.
- 25. (Amended) A waveguide as claimed in claim 1, wherein the thickness of the second core layer is in the range  $0.2\mu m$  to  $30\mu m$ .
- 26. (Amended) A waveguide as claimed in Claim 24, wherein the width of the waveguide core lies in the range 0.4μm to 60μm.
- 28. (Amended) A waveguide as claimed in claim 1, wherein the refractive index of the substrate and the refractive index of the upper cladding layer are substantially equal.
- 29. (Amended) An optical waveguide according to Claim 1, wherein the first core layer includes at least 17% wt germanium dopant.
- 33. (Amended) A method as claimed in Claim 30, wherein the formation of the substrate includes the formation of an intermediate layer formed on said substrate including the formation of a buffer layer which is formed by thermally oxidising the substrate.
- 36. (Amended) A method as claimed in Claim 33, wherein the formation of the intermediate layer further includes the formation of a lower cladding layer formed on said buffer layer.

- 39. (Amended)A method as claimed in Claim 30, wherein the second core layer is formed on the first core layer and wherein the first core layer is formed on the substrate, and wherein a further first core layer is formed on the second core layer such that the first core layer sandwiches the second core layer.
- 42. (Amended) A method as claimed in Claim 30, wherein the steps of forming any one of the substrate, first core layer, the second core layer, and the upper cladding layer comprise the steps of: depositing each layer; and at least partially consolidating each layer.
- 50. (Amended) A method as claimed in Claim 30, wherein the concentration of the first core layer dopant is selectively controlled during the formation of the first core layer and the concentration of the second core layer dopant is selectively controlled during the formation of the second core layer so that the refractive index of the first core layer and the refractive index of the second core layer are substantially equal.
- 53. (Amended) A method as claimed in Claim 42, wherein at least one of the substrate, the first core layer, the second core layer, and the upper cladding layer is deposited by a Flame Hydrolysis Deposition process and/or Chemical Vapour Deposition process.
- 55. (Amended) A method as claimed in Claim 42, wherein the consolidation is by fusing using a Flame Hydrolysis Deposition burner.
- 57. (Amended) A method as claimed in Claim 54, wherein the step of fusing the lower cladding layer and the step of fusing the first core layer and/or the second core layer are performed simultaneously.
- 58. (Amended) A method as claimed in Claims 30, wherein the waveguide core is formed from the first core layer and the second core layer using a dry etching technique and/or a photolithographic technique and/or a mechanical sawing process.

62. (Amended) A laser waveguide with multiple core layers for transmitting an optical signal, the laser waveguide comprising a waveguide as claimed in claim 1, the laser waveguide further comprising:

at least one grating formed in said waveguide core.

- 65. (Amended) A laser waveguide as claimed in Claim 63, wherein the interference mirror is butt-coupled to or directly deposited at the input of the waveguide.
- 66. (Amended) A laser waveguide as claimed in Claim 62, wherein the laser waveguide includes two mirrors and a grating.
- 67. (Amended) A laser waveguide as claimed in Claim 62, wherein the laser waveguide includes one mirror and two gratings.
- 69. (Amended) A laser waveguide as claimed in Claim 62, wherein the grating formed is a Bragg grating.
- 70. (Amended) A laser waveguide as claimed in Claim 62, wherein said grating forms an output coupler for said laser waveguide.
- 71. (Amended) A laser waveguide as claimed in Claim 62, further comprising an optical interference mirror butt coupled to or directly deposited at the output of the waveguide.
- 72. (Amended) A method of fabricating a laser waveguide, comprising forming a waveguide according to a method as claimed in Claim 30, the method of fabricating the laser waveguide further including the steps of:

forming at least one grating in said waveguide core, wherein the grating is formed using a laser operating at a wavelength in the range of 150 nm to 400 nm through a phase mask deposited on top of said upper cladding layer of the waveguide.

77. (Amended) A method as claimed in Claims 72, wherein the grating is formed using a using an interference side writing technique.

## OSESOES Attorney Docket No. MCW-002US

78. (Amended) A method as claimed in Claim 72, wherein the grating is formed using a direct writing technique.

Please cancel claims 6, 7, 15, 18, 19, 27, 34, 35, 37, 38, 40, 41, 44-49, 52, 56, 60, 61, 64, 68, 73-76, 79-85.

#### REMARKS

Applicants amend the claims to remove multiple dependencies, to provide proper antecedent basis, and to address other matters of form. The foregoing amendments introduce no new matter and are not related to issues of patentability.

Entry of the foregoing Preliminary Amendment is respectfully in order and requested.

If there are any questions regarding the amendments to the application, we invite the Examiner to call Applicant's representative at the telephone number below.

Respectfully submitted,

LAHIVE & COCKFIELD, LLP

Anthony A. Laurentano Registration No. 38,220

Attorney for Applicants

28 State Street Boston, MA 02109 (617) 227-7400

Date: August 3, 2001

#### Version With Markings To Show Changes Made

Please amend claims 4, 5, 8-11, 13, 14, 16, 17, 20-26, 28, 29, 33, 36, 39, 42, 50, 53, 55, 57, 58, 62, 65-67, 69-72, 77 and 78 as follows:

- 4. A waveguide as claimed in any preceding claim 1, wherein the substrate comprises silicon and/or silica and/or sapphire.
- 5. A waveguide as claimed in any preceding claim 1, wherein the substrate includes an intermediate layer, including a buffer layer formed on the substrate, wherein said buffer layer comprises a thermally oxidised layer of the substrate.
- 8. A waveguide as claimed in Claim 6 or Claim 7 5, wherein the intermediate layer further includes a lower cladding layer formed on said buffer layer.
- 9. A waveguide as claimed in any of Claims 6 to 8 5, wherein the thickness of the buffer layer is in the range  $5m 5\mu m$  to  $20m 20\mu m$ .
- 10. A waveguide as claimed in any preceding claim 1, wherein the second core layer is formed on the first core layer and said first core layer is formed on the substrate.
- 11. A waveguide as claimed in any of Claims 1 to 9, wherein the first core layer is formed on the second core layer and said second core layer is formed on the substrate.
- 13. A waveguide as claimed in any preceding claim 1, wherein the first core layer includes silica.
- 14. A waveguide as claimed in any preceding claim 1, wherein the first core layer dopant includes dopant ions, including tin and/or cerium and/or sodium.

- 16. A waveguide as claimed in any preceding claim 1, wherein the second core layer includes silica.
- 17. A waveguide as claimed in any preceding claim  $\underline{1}$ , wherein the second core layer includes a phosphorus oxide.
- 20. A waveguide as claimed in any of Claims 16 to 19, wherein the second core layer dopant includes a rare earth and/or a heavy metal and/or compounds of these elements.
- 21. A waveguide as claimed in Claim 20-16, wherein the second core layer dopant includes rare earth is Erbium or Neodymium.
- 22. A waveguide as claimed in any preceding claim 1, wherein the refractive indices of the first core layer and the second core layer are substantially equal.
- 23. 18. A waveguide as claimed in any preceding claim 1, wherein the refractive index of the waveguide core differs from that of the substrate by at least 0.05%.
- 24. A waveguide as claimed in any preceding claim  $\underline{1}$ , wherein the thickness of the first core layer is in the range  $\underline{0.2m}$   $\underline{0.2\mu m}$  to  $\underline{30m}$   $\underline{30\mu m}$ .
- 25. A waveguide as claimed in any preceding claim 1, wherein the thickness of the second core layer is in the range 0.2m  $0.2\mu m$  to 30m  $30\mu m$ .
- 26. A waveguide as claimed in Claim  $24,\underline{19}$  wherein the width of the waveguide core lies in the range 0.4m 0.4µm to 60m  $\underline{60}$ µm.
- 28. A waveguide as claimed in any preceding claim 1, wherein the refractive index of the substrate and the refractive index of the upper cladding layer are substantially equal.

- 29. An optical waveguide according to any of Claims 1 to 28, wherein the first core layer includes at least 17% wt germanium dopant.
- 33. A method as claimed in any of Claims 30 to 32, wherein the formation of the substrate includes the formation of an intermediate layer formed on said substrate including the formation of a buffer layer which is formed by thermally oxidising the substrate.
- 36. A method as claimed in Claim 34 or Claim 35 33, wherein the formation of the intermediate layer further includes the formation of a lower cladding layer formed on said buffer layer.
- 39. A method as claimed in any of Claims 30 to 38, wherein the second core layer is formed on the first core layer and wherein the first core layer is formed on the substrate, and wherein a further first core layer is formed on the second core layer such that the first core layer sandwiches the second core layer.
- 42. A method as claimed in any of Claims 30 to 41, wherein the steps of forming any one of the substrate, first core layer, the second core layer, and the upper cladding layer comprise the steps of: depositing each layer; and at least partially consolidating each layer.
- 50. A method as claimed in any of Claims 30-to 49, wherein the concentration of the first core layer dopant is selectively controlled during the formation of the first core layer and the concentration of the second core layer dopant is selectively controlled during the formation of the second core layer so that the refractive index of the first core layer and the refractive index of the second core layer are substantially equal.
- 53. A method as claimed in any of Claims 42 to 52, wherein at least one of the substrate, the first core layer, the second core layer, and the upper cladding layer is deposited by a Flame Hydrolysis Deposition process and/or Chemical Vapour Deposition process.

- 55. A method as claimed in any of Claims 42 to 54, wherein the consolidation is by fusing using a Flame Hydrolysis Deposition burner.
- 57. A method as claimed in Claim 55 or Claim 56-54, wherein the step of fusing the lower cladding layer and the step of fusing the first core layer and/or the second core layer are performed simultaneously.
- 58. A method as claimed in any of Claims 30-to-57, wherein the waveguide core is formed from the first core layer and the second core layer using a dry etching technique and/or a photolithographic technique and/or a mechanical sawing process.
- 62. A laser waveguide with multiple core layers for transmitting an optical signal, the laser waveguide comprising a waveguide as claimed in any of claims 1 to 29, the laser waveguide further comprising:

at least one grating formed in said waveguide core.

- 65. A laser waveguide as claimed in Claim 63-64, wherein the interference mirror is butt-coupled to or directly deposited at the input of the waveguide.
- 66. A laser waveguide as claimed in any of Claims 62-to-65, wherein the laser waveguide includes two mirrors and a grating.
- 67. A laser waveguide as claimed in any of Claims 62-to 65, wherein the laser waveguide includes one mirror and two gratings.
- 69. A laser waveguide as claimed in any of Claims 62-to-68, wherein the grating formed is a Bragg grating.
- 70. A laser waveguide as claimed in any of Claims 62 to 69, wherein said grating forms an output coupler for said laser waveguide.
- 71. A laser waveguide as claimed in any of Claims 62-to 70, further comprising an optical interference mirror butt coupled to or directly deposited at the output of the waveguide.

72. A method of fabricating a laser waveguide, comprising forming a waveguide according to a method as claimed in any of Claims 30 to 61, the method of fabricating the laser waveguide further including the steps of:

forming at least one grating in said waveguide core, wherein the grating is formed using a laser operating at a wavelength in the range of 150 nm to 400 nm through a phase mask deposited on top of said upper cladding layer of the waveguide.

- 77. A method as claimed in any of Claims 72-to 74, wherein the grating is formed using a using an interference side writing technique.
- 78. A method as claimed in any of Claims 72-to 74, wherein the grating is formed using a direct writing technique.

Please cancel claims 6, 7, 15, 18, 19, 27, 34, 35, 37, 38, 40, 41, 44-49, 52, 56, 60, 61, 64, 68, 73-76, 79-85.

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1	OPTICAL WAVEGUIDE WITH MULTIPLE CORE LAYERS AND METHOD
2	OF FABRICATION THEREOF
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5	FIELD OF THE INVENTION
6	
7	This invention relates to an optical waveguide with
8	multiple core layers and a method of fabrication
9	thereof.
.0	
.1	In particular, the invention relates to a doped planar
2	waveguide with multiple core layers and which includes
L3	both active and passive components and to a method of
L <b>4</b>	fabricating a planar waveguide for an optical circuit
L5	in which the core is composed of layers of different
L6	materials.
L7	
L8	
L9	BACKGROUND OF THE INVENTION
20	
21	Planar waveguides can be passive devices or can
22	include active components; for example, modulators,
23	couplers, and switches. Planar waveguides
24	incorporating active components are extremely
25	advantageous as they can be used to provide integrated
26	

optic packages which can serve as complete transmitting

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- 2 modules with, for example, components for amplitude or
- 3 phase modulation, or multiplexing in an optical
- 4 communication network.

5

- 6 Rare earth doped fibre amplifiers, for example erbium
- 7 or neodymium doped fibre amplifiers, are known to have
- 8 several advantages in optical communication networks
- 9 such as high gain, low noise, high power conversion
- 10 efficiency and wide spectral bandwidth. The present
- invention seeks to provide the same advantages in
- 12 planar rare earth doped waveguides and moreover to
- provide a laser waveguide amplifier which can be used,
- 14 for example, in an optical communication network to
- 15 amplify attenuated signals.

16

- 17 Planar wavequide technology is important in the
- 18 fabrication of lasers and optical amplifiers due to the
- 19 superior stability, compact geometry of planar
- 20 wavequide technology. Also, active components, for
- 21 example modulators, can be integrated into the planar
- 22 device.

23

- 24 A variety of techniques, including flame hydrolysis
- deposition (FHD), sputtering, plasma enhanced chemical
- 26 vapour deposition (CVD) and ion-exchange can be used in
- the fabrication of silica-based planar waveguides doped
- with rare-earth ions and which display laser
- 29 characteristics.

- In such laser amplifying waveguides, it is desirable to
- 32 obtain a high concentration of rare earth ions in order
- 33 to achieve very compact and efficient devices.
- 34 However, high concentrations of rare earth ions in a
- 35 waveguide layer with relatively low solubility can
- 36 result in the formation of clusters of rare earth ions.

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The interaction between the rare earth ions in such 1 2 clusters quenches the excited state required for the 3 lasing process and thus degrades the optical amplification provided by the waveguide. 4 5 Other complications arise in the fabrication of laser 6 7 waveguides for applications which require single mode transmission, narrow spectral bandwidths, and/or 8 precise control of the lasing wavelength depend 9 critically on their cavity type. Laser waveguides 10 which have butt-coupled mirrors on the waveguide ends 11 or dielectric reflection mirrors are known in the art 12 but suffer to a greater or lesser degree from certain 13 disadvantages; for example, low spectral selectivity. 14 15 Bragg gratings incorporated in a waveguide core can 16 provide enhanced spectral selectivity. The fabrication 17 of such gratings is affected by the host glass 18 composition present in the waveguide core which 19 determine the UV absorption band of the core material 20 and thus its photosensitive properties. For example, 21 22 if phosphorus is used as a core dopant ion it can alleviate the formation of rare earth ion clusters but 23 has the disadvantage that it reduces the amount of 24 absorption in the UV and thus reduces the 25 photosensitivity of the core. If germanium is used as 26 a core dopant ion it can increase the photosensitivity 27 of the core but has the disadvantage of promoting rare 28 earth cluster formation. 29 30 The introduction of a Bragg grating can be effected in 31 a planar waveguide by a number of known methods which 32 suffer to a greater or lesser degree from certain 33 disadvantages. The invention provides an optical 34 waveguide with multiple core layers which is suitable 35 for forming a laser waveguide with a high degree of 36

spectral selectivity. The waveguide core combines two 1 different types of silica based layers and these core 2 3 layers obviate or mitigate the aforementioned disadvantages which arise when seeking to fabricate an 4 in-core Bragg grating to enhance the spectral 5 selectivity of the laser waveguide. The waveguide 6 7 formed enables in-core Bragg grating formation at a 8 range of UV wavelengths above 150 nm. 9 10 SUMMARY OF THE INVENTION 11 In accordance with a first aspect of the invention 12 13 there is provided an optical waveguide with multiple core layers comprising: a substrate; a waveguide core 14 15 formed on said substrate; and an upper cladding layer 16 embedding said waveguide core; wherein said waveguide core comprises a first core layer and a second core 17 18 layer. 19 20 Preferably, the substrate comprises silicon and/or silica and/or sapphire. 21 22 Preferably, the substrate includes an intermediate 23 The intermediate layer may include a buffer 24 layer formed on the substrate. The buffer layer may 25 comprise a thermally oxidised layer of the substrate. 26 27 The intermediate layer may further include a lower 28 cladding layer formed on said buffer layer. 29 30 Preferably, the thickness of the buffer layer is in the 31 32 range 5  $\mu$ m to 20  $\mu$ m. 33 34 The second core layer may be formed on the first core layer and said first core layer may be formed on the 35

substrate. Alternatively, the first core layer may be

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formed on the second core layer and said second core 1 layer may be formed on the substrate. A further first 2 core layer may be formed on the second core layer such 3 that the first core layer sandwiches the second core 4 5 layer. 6 Preferably, the first core layer includes a dopant to 7 8 permit the first core layer to exhibit a photosensitive The first core layer may include silica. 9 response. 10 Preferably, the first core layer includes a germanium 11 oxide and/or a boron oxide. The first core layer 12 dopant may include dopant ions. Preferably, the first 13 core layer dopant ions include tin and/or cerium and/or 14 sodium. 15 16 The second core layer may include a dopant to induce 17 amplification of an optical signal transmitted through 18 said waveguide core. The second core layer may include 19 silica. The second core layer may include a phosphorus 20 The second core layer dopants may include 21 The second core layer dopant may include 22 dopant ions. a mobile dopant. 23 24 Preferably, the second core layer dopants include a 25 rare earth and/or a heavy metal and/or compounds of 26 these elements. More preferably, the rare earth is 27 Erbium or Neodymium. 28 29 Preferably, the refractive indices of the first core 30 layer and the second core layer are substantially 31 32 equal. 33 Preferably, the refractive index of the waveguide core 34 differs from that of the substrate by at least 0.05%.

6

1 Preferably, the thickness of the first core layer is in the range 0.2  $\mu m$  to 30  $\mu m$ .

3

4 Preferably, the thickness of the second core layer is in the range 0.2  $\mu m$  to 30  $\mu m$ .

6

Preferably, the width of the waveguide core lies in the range 0.4  $\mu m$  to 60  $\mu m$ .

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The upper cladding layer and the lower cladding layer may comprise the same material. The refractive index of the substrate and the refractive index of the upper cladding layer may be substantially equal.

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In accordance with a second aspect of the invention there is provided a method of fabricating a waveguide comprising the steps of: providing a substrate; forming a waveguide core on the substrate; and forming an upper cladding layer to embed the waveguide core, wherein the waveguide core is formed from a first core layer and a second core layer.

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The formation of the substrate may include the formation of an intermediate layer formed on said substrate. The formation of the intermediate layer may include the formation of a buffer layer. The buffer layer may be formed by thermally oxidising the substrate.

29

The formation of the intermediate layer may further include the formation of a lower cladding layer formed on said buffer layer. The formation of the lower cladding layer may include doping said lower cladding layer with a dopant. The dopant may include dopant ions.

1	Preferably, the second core layer is formed on the
2	first core layer and the first core layer is formed on
3	the substrate. Alternatively, the first core layer may
4	be formed on the second core layer and said second core
5	layer may be formed on the substrate.
6	
7	A further first core layer may be formed on the second
8	core layer such that the first core layer sandwiches
9	the second core layer.
10	
11	The steps of forming any one of the substrate, first
12	core layer, the second core layer, and the upper
13	cladding layer may comprise the steps of:
14	depositing each layer; and
15	at least partially consolidating each layer.
16	
17	Preferably, any one of the substrate, the first core
18	layer, the second core layer and the upper cladding
19	layer partially consolidated after deposition is fully
20	consolidated with the full consolidation of any other
21	of the first core layer, the second core layer or the
22	upper cladding layer.
23	
24	Preferably, the formation of the first core layer
25	includes the doping of the first core layer with a
26	dopant.
27	
28	Preferably, the first core layer dopant permits the
29	first core layer to exhibit a photosensitive response.
30	
31	Preferably, the formation of the second core layer
32	includes the doping of the second core layer with a
33	dopant.
34	
35	Preferably, the second core layer dopant induces
36	amplification of an optical signal transmitted through

8

said waveguide core.

3 The formation of the substrate may include the doping

4 of the substrate with a dopant. The dopant may include

5 dopant ions.

6

2

7 Preferably, the substrate dopant includes a mobile

8 dopant.

9

10 Preferably, said first core layer dopant ions include

11 tin and/or cerium and/or sodium.

12

13 Preferably, said second core layer dopant ions include

14 a rare earth and/or a heavy metal and/or compounds

15 thereof.

16

17 Preferably, said rare earth is Erbium and/or Neodymium.

18

19 Preferably, the concentration of the first core layer

20 dopant is selectively controlled during the formation

of the first core layer and the concentration of the

22 second core layer dopant is selectively controlled

23 during the formation of the second core layer so that

24 the refractive index of the first core layer and the

25 refractive index of the second core layer are

26 substantially equal.

27

28 Preferably, the concentrations of the first core layer

29 dopant and second core layer dopant are controlled to

30 give a refractive index for the waveguide core which

31 differs from that of the substrate layer by at least

32 0.05%.

33

34 The lower cladding layer and said buffer layer may be

formed substantially in the same step. At least one of

36 the substrate, the first core layer, the second core

layer, and the upper cladding layer may be deposited by

9

- 2 a Flame Hydrolysis Deposition process and/or Chemical
- 3 Vapour Deposition process. The Chemical Vapour
- 4 Deposition process may be a Low Pressure Chemical
- 5 Vapour Deposition process or a Plasma Enhanced Chemical
- 6 Vapour Deposition process.

7

- 8 Preferably, the consolidation is by fusing using a
- 9 Flame Hydrolysis Deposition burner. Alternatively, the
- 10 consolidation may be by fusing in a furnace.

11

- 12 The step of fusing the lower cladding layer and the
- 13 step of fusing the first core layer and/or the second
- 14 core layer may be performed simultaneously. The
- 15 waveguide core may be formed from the first core layer
- and the second core layer using a dry etching technique
- 17 and/or a photolithographic technique and/or a
- 18 mechanical sawing process. The dry etching technique
- 19 may comprise a reactive ion etching process and/or a
- 20 plasma etching process and/or an ion milling process.

21

- 22 The waveguide core formed from the first core layer and
- 23 the second core layer may be square or rectangular in
- 24 cross-section.

25

- 26 In accordance with a third aspect of the invention
- there is provided a laser waveguide with multiple core
- 28 layers comprising a waveguide according to the first
- 29 aspect of the invention, the laser waveguide further
- 30 comprising:
- at least one grating formed in said waveguide
- 32 core.

33

- 34 Preferably, the laser waveguide further comprises at
- 35 least one optical interference mirror.

10

More preferably, the optical interference mirror is 1 2 provided at the input of the waveguide. 3 interference mirror may be butt-coupled to or directly deposited at the input of the waveguide. 4 5 6 The laser waveguide may include two mirrors and a 7 grating. Alternatively, the laser waveguide may 8 include one mirror and two gratings. Alternatively. 9 the laser waveguide may include three gratings. grating formed may be a Bragg grating. The grating may 10 11 form an output coupler for said laser waveguide. 12 13 The laser waveguide may further comprise an optical 14 interference mirror butt coupled to or directly 15 deposited at the output of the waveguide. 16 In accordance with a fourth aspect of the invention 17 there is provided method of fabricating a laser 18 19 waveguide, comprising forming a waveguide according to the method of the second aspect of the invention, the 20 21 method of fabricating the laser waveguide further 22 including the steps of: 23 forming at least one grating in said waveguide 24 core. 25 26 The method may further include the step of attaching at 27 least one optical interference mirror to the wavequide. 28 The optical interference mirror may be attached to an 29 30 input of the wavequide. 31 32 The grating may be formed using a laser operating at a wavelength in the range of 150 nm to 400 nm through a 33 phase mask deposited on top of said upper cladding 34 layer of the waveguide. The mask may be a quartz mask. 35 36 The grating may be formed using a using an interference

1	side writing technique. The grating may be formed
2	using a direct writing technique. The grating formed
3	may be a Bragg grating.
4	
5	Preferably, in the above method, the optical
6	interference mirror is butt-coupled to or directly
7	deposited at the input of the waveguide.
8	
9	The method may further comprise the step of attaching a
10	second optical interference mirror to the output of the
11	waveguide.
12	
13	DESCRIPTION OF THE DRAWINGS
14	
15	Embodiments of the present invention will now be
16	described, by way of example only, with reference to
<b>17</b> .	the accompanying drawings, in which:-
18	
19	Figs. 1A to 1C are schematic cross-sectional diagrams
20	of a waveguide with multiple core layers during various
21	stages of fabrication.
22	
23	Fig. 2A is a schematic representation of a laser
24 '	waveguide formed from the waveguide shown in Figs. 1A
25	to 1C; and
26	
27	Fig. 2B is a detail, to an enlarged scale, of the
28	structure shown in Fig. 2A.
29	
30	
31	DETAILED DESCRIPTION OF THE INVENTION
32	
33	Referring now to the drawings, Figs. 1A to 1C
34	illustrate schematically stages in the fabrication of a
35	waveguide with a multi-layered core according to the
36	invention.

12

1 Referring now to Fig. 1A, there is illustrated a 2 waveguide 1 which is fabricated from a substrate 2. The substrate 2 comprises a silicon wafer. However, 3 other suitable substrates including silica and 4 5 sapphire, may be used. 6 A silica buffer layer 3, comprising a thermally 7 8 oxidised layer of the substrate 2, is formed on the 9 substrate 2. The thickness of the buffer layer 3 is 15 10  $\mu$ m which lies in a preferred range of 5  $\mu$ m to 20  $\mu$ m. 11 A suitable method, for example, a flame hydrolysis 12 deposition (FHD) method, is used to deposit a first 13 core layer 4 on top of the buffer layer 3. 14 thickness of the first core layer 4 is 2  $\mu$ m which lies 15 in a preferred range of 0.2  $\mu m$  to 30  $\mu m$ . 16 17 The material included in the first core layer 4 18 provides a high photosensitive response to an optical 19 In a preferred embodiment, the first core 20 layer 4 includes a high concentration of Germanium 21 dopant, for example 17 %wt, co-doped with Boron, for 22 example 5 %wt. Other dopant ions can be included, or a 23 mixture of dopant ions, for example, tin, cerium, 24 and/or sodium. 25 26 The dopant and co-dopants are introduced during the 27 28 deposition of the first core layer 4. The Germanium dopant induces a high photosensitive response and the 29 Boron co-dopant lowers the refractive index induced by 30 the high level of Germanium in the first core layer 4. 31 The concentrations of the dopant and co-dopant are 32 33 adjusted to 17% wt and 5% wt to give a difference between the refractive index of the first core layer 4 34 and the refractive index of the buffer layer 3 of 0.75% 35

which lies in a preferred range of 0.05% to 2.0%.

13

- 1 The first core layer 4 is then consolidated by a
- 2 suitable method, for example by a second pass of the
- 3 FHD burner or by consolidating the waveguide 1 in an
- 4 electrical furnace.

5

- 6 Fig. 1B shows a further stage in the fabrication of the
- 7 wavequide 1 in which a second core layer 5 is formed on
- 8 the first core layer 4.

9

- 10 The second core layer 5 is deposited on the first core
- layer 4 using a suitable method, for example FHD, and
- is then suitably consolidated, for example, in an
- 13 electrical furnace.

14

- 15 The second core layer 5 is doped with rare earth dopant
- 16 ions, for example Er<sup>+3</sup>, using an aerosol doping
- 17 technique, and co-doped, for example, with Phosphorus
- during the deposition of the second core layer 5. The
- 19 thickness of the second core layer 5 is  $4\mu m$ , which lies
- 20 in the range of  $0.2\mu m$  to  $30\mu m$ .

- 22 Alternative methods can be used to dope the second core
- layer 5 such as solution doping. Preferably, the dopant
- 24 and co-dopant are simultaneously introduced in a
- 25 controlled manner during the deposition of the second
- 26 core layer 5. The concentrations of the dopant and co-
- 27 dopant can be controlled so that the second core layer
- 28 5 provides the desired signal gain for optical signals
- 29 propagating through the waveguide and also to ensure
- 30 that the refractive index of the second core layer 5 is
- 31 matched to the refractive index of the first core layer
- 32 4. In this embodiment, the indices are substantially
- 33 matched. Alternatively, the first core layer 4 and the
- 34 second core layer 5 can be subjected to a further
- 35 process, for example, UV trimming, to effect matching
- 36 of their refractive indices.

14

The photosensitive response of the first core layer 4 in combination with the optical signal gain of the second core layer 5 effect the overall level of optical signal amplification provided by the waveguide 1.

5

A waveguide core 6 is then formed from the first core 6 layer 4 and the second core layer 5 by using a suitable 7 method, for example conventional photolithographic 8 and/or reactive ion etching (RIE) methods. A portion 9 of the second core layer 5 is suitably masked and the 10 unwanted portions of the second core layer 5 and the 11 underlying first core layer 4 are etched away to leave 12 the wavequide core 6. The overall dimensions of the 13 wavequide core 6 formed are  $6\mu m \times 6\mu m$  which is in a 14 preferred range of  $0.4\mu m \times 0.4\mu m$  to 60  $\mu m \times 60\mu m$ . 15

16 17

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19 20

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24

The co-dopant, here Boron, in the first core layer 4 reduce the refractive index of the waveguide core 6 and enable single mode operation even for large waveguide cores, for example waveguide cores whose dimensions are in the range of  $0.4\mu \text{m} \times 0.4\mu \text{m}$  to 60  $\mu \text{m} \times 60\mu \text{m}$ . The co-dopant in the first core layer 4 can also provide other advantages such as enabling higher refractive index changes to occur during later stages of fabrication of a waveguide with multiple core layers.

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The first core layer 4 effectively can reduce the optical signal gain provided by the second core layer 5. It is thus advantageous for the first core layer 4 to be as photosensitive as possible in particular as the refractive index modulation no longer occurs over the entire volume of the waveguide core 6.

32 33

Fig. 1C shows a further stage in the fabrication of the waveguide. An upper cladding layer 7 is deposited on the waveguide core 6 using an FHD method. The upper

15

- 1 cladding layer 7 embeds the waveguide core 6. The
- 2 upper cladding layer 7 is doped during deposition, for
- 3 example with Phosphorus and Boron, to adjust its
- 4 refractive index until the refractive index of the
- 5 upper cladding layer 7 matches the refractive index of
- 6 the buffer layer 3. The upper cladding layer 7 is then
- 7 consolidated, for example in an electrical furnace.

8

- 9 In a second preferred embodiment of the invention, a
- 10 lower cladding layer is formed on top of the buffer
- layer 3 before the first core layer 4 is deposited and
- in which the level of dopant in the upper cladding
- layer 7 is adjusted until the refractive index of the
- 14 upper cladding layer 7 matches that of the lower
- 15 cladding layer. The lower cladding layer can be
- deposited and consolidated using the same techniques as
- 17 the upper cladding layer 7.

18

- 19 In an alternative layer structure the first core layer
- 20 4 may be deposited on top of the second core layer 5 or
- 21 respective first core layers 4 may be provided both
- below and on top of the second core layer 5. The core
- layer 5 is then sandwiched between two photo-sensitive
- 24 first core layers 4 increasing the coupling coefficient
- 25 of the device.

26

- 27 It is possible also, for certain applications, to dope
- 28 the photo-sensitive first core layer 4 with a small
- 29 amount of rare earth ions.

- 31 Referring now to Figs. 2A and 2B of the drawings, there
- 32 is shown a schematic diagram of laser waveguide
- 33 according to the invention. Figs. 2A and 2B show a
- 34 cross-section parallel to the longitudinal axis of the
- 35 laser wavequide core, such that the wavequide core is
- 36 seen only in profile.

16

1 Fig. 2A shows a planar laser waveguide 10 incorporating

- 2 a Bragg grating 11. The laser waveguide 10 includes a
- 3 silicon substrate layer 12 and a silica buffer layer 13
- 4 comprising a thermally oxidised layer of the substrate
- 5 12. The buffer layer 13 is formed on the substrate
- 6 layer 12.

7

8 Fig. 2B is an enlarged view of a section of Fig. 2A. A

- 9 first core layer 14 is deposited and consolidated on
- the buffer layer 13 and second core layer 15 is
- 11 deposited and consolidated on the first core layer 14
- using the techniques described above for the deposition
- and consolidation of first and second core layers 4 and
- 14 5 in the waveguide 1. The first core layer 14 can
- 15 alternatively be formed on an lower cladding layer (not
- shown) formed on buffer layer 13.

17

18 The second core layer 15 is doped with neodymium

- instead of the erbium used as a dopant in the second
- 20 core layer 5. Fig. 2A represents a cross-section
- 21 through the laser waveguide 10 parallel to the
- 22 direction of light propagation through the waveguide 10
- 23 (i.e., normal to the cross-sectional plane through the
- 24 waveguide shown in Fig. 1C). The waveguide core 16 is
- 25 formed from said first core layer 14 and said second
- 26 core layer 15 using the same technique described above
- for the formation of the first core layer 4 and the
- 28 second core layer 15.

29

- 30 An upper cladding layer 17 is then deposited on the
- 31 second core layer 15 and the grating 11. The upper
- 32 cladding layer 17 is deposited and consolidated using
- 33 the same methods as described above for the deposition
- 34 and consolidation of the upper cladding layer 7 in the
- 35 fabrication of waveguide 1.

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17 The laser cavity of the laser waveguide 10 is 1 fabricated by writing the Bragg grating 11 into a 2 generally central portion of the first core layer 14 3 and the second core layer 15. Conventionally, the 4 5 Bragg grating 11 may be written using a KrF excimer laser operating at 248 nm through a quartz phase mask 6 7 deposited on top of the upper cladding layer. 8 9 An input 18 of the laser waveguide 10 provides an 10 11 optical signal at a pump wavelength to the laser 12 wavequide 10. An optical interference mirror 19 buttcoupled to the input end 18 of the laser waveguide 10 13 has a high reflectivity ( $R_{sig} = 99.9$ %) around the maxima 14 of the desired output wavelength and has a high 15 transmittance at the pump wavelength  $(T_{pump} > 95\%)$ . 16 grating 11 forms an output coupler at the output 20 of 17 18 the laser waveguide 10. 19 20 The grating 11 is designed for use at 1050 nm and the 21 reflectivity of the grating 11 formed saturates at 80%. The phase mask used to form the grating 11 has a pitch 22 In other embodiments, however, it is 23 of 720 nm. possible to form gratings 11 which can be used at a 24 wavelength in the range of 500 nm to 2100 nm by using 25 suitable phase masks. 26 27 In another embodiment of a laser waveguide, a grating 28 11 can be provided at both the input 18 and the output 29 30 20 of the laser waveguide 10, preferably with both gratings having substantially the same Bragg wavelength 31 thus providing a distributed Bragg reflection laser 32 33 (DBR). 34 35 In yet another embodiment, a distributed feedback laser (DFB) can also be formed by having a grating extending 36

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along the length of the gain cavity formed by the core 1 2 layer 5. 3 4 Further, a multicavity laser can be formed by butt-5 coupling another mirror to the output end of the laser waveguide 10. These external mirrors can be bulk 6 mirror butt-coupled or mirrors directly deposited on 7 the ends of the waveguide. A multiple wavelength laser 8 can be provided by photoimprinting a sampled grating in 9 the waveguide core, with precise control of channel 10 spacing. Additionally, a multiple wavelength laser can 11 be achieved by exposing the same core area to very 12 similar UV patterns, with each exposure determining 13 each one of the emission wavelengths of the 14 superimposed Bragg gratings. An additional grating can 15 be defined to provide gain equalisation for the several 16 17 wavelengths. 18 Thus, a multicavity laser can be constructed by using 19 two mirrors and a grating, one mirror and two gratings, 20 or indeed three gratings. 21 22 23 Still further, in a different application, for example, optical amplifiers, a grating can also be formed on the 24 first core layer 4 to act as a "tap" to flatten optical 25 26 gain spectra. 28

27

While several embodiments of the present invention have been described and illustrated, it will be apparent to 29 those skilled in the art once given this disclosure 30 that various modifications, changes, improvements and 31 32 variations may be made without departing from the spirit or scope of this invention. 33

### ATT 24 AMOT

Claims

2		
3	l.	An optical waveguide with multiple core layers for
4		transmitting an optical signal, the waveguide
5		including:
6		a substrate;
7		a waveguide core formed on the substrate and comprising
8		a first core layer and a second core layer;
9		an upper cladding layer embedding said waveguide core;
10		wherein the first core layer includes a dopant to
11		permit the first core layer to exhibit a photosensitive
12		response, and the second core layer includes a dopant
13		to induce amplification of an optical signal
14		transmitted through said waveguide core.
15		
16	2.	An optical waveguide according to Claim 1, wherein the
17		first core layer includes a germanium oxide to permit
18		the first core layer to exhibit a photosensitive
19		response.
20		
21	з.	An optical waveguide according to Claim 2, wherein the
22		first core layer further includes a boron oxide.
23		
24	4.	A waveguide as claimed in any preceding claim, wherein
25		the substrate comprises silicon and/or silica and/or
26		sapphire.
27		
28	5.	A waveguide as claimed in any preceding claim, wherein
29		the substrate includes an intermediate layer.
30		

1 6. A waveguide as claimed in Claim 5, wherein the
2 intermediate layer includes a buffer layer formed on
3 the substrate.

4

7. A waveguide as claimed in Claim 6, wherein said buffer
 layer comprises a thermally oxidised layer of the
 substrate.

8

9 8. A waveguide as claimed in Claim 6 or Claim 7, wherein
10 the intermediate layer further includes a lower
11 cladding layer formed on said buffer layer.

12

13 9. A waveguide as claimed in any of Claims 6 to 8, wherein 14 the thickness of the buffer layer is in the range 5 m 15 to 20 m.

16

17 10. A waveguide as claimed in any preceding claim, wherein 18 the second core layer is formed on the first core layer 19 and said first core layer is formed on the substrate.

20

21 11. A waveguide as claimed in any of Claims 1 to 9, wherein 22 the first core layer is formed on the second core layer 23 and said second core layer is formed on the substrate.

24

25 12. A waveguide as claimed in Claim 10, wherein a further
26 first core layer is formed on the second core layer
27 such that the first core layer sandwiches the second
28 core layer.

29

30 13. A waveguide as claimed in any preceding claim, wherein
31 the first core layer includes silica.

1 14. A waveguide as claimed in any preceding claim, wherein 2 the first core layer dopant includes dopant ions.

3

4 15. A waveguide as claimed in Claim 14, wherein the first core layer dopant ions include tin and/or cerium and/or sodium.

7

8 16. A waveguide as claimed in any preceding claim, wherein 9 the second core layer includes silica.

) 10

11 17. A waveguide as claimed in any preceding claim, wherein 12 the second core layer includes a phosphorus oxide.

13

14 18. A waveguide as claimed in any preceding claim, wherein the second core layer dopant includes dopant ions.

16

17 19. A waveguide as claimed in Claim 18, wherein the second core layer dopant includes a mobile dopant.

19

20 20. A waveguide as claimed in any of Claims 16 to 19,
21 wherein the second core layer dopant includes a rare
22 earth and/or a heavy metal and/or compounds of these
23 elements.

24

25 21. A waveguide as claimed in Claim 20, wherein the rare earth is Erbium or Neodymium.

27

28 22. A waveguide as claimed in any preceding claim, wherein 29 the refractive indices of the first core layer and the 30 second core layer are substantially equal.

A waveguide as claimed in any preceding claim, wherein ı the refractive index of the waveguide core differs from 2 that of the substrate by at least 0.05%. 3

4 A waveguide as claimed in any preceding claim, wherein 5 the thickness of the first core layer is in the range

0.2 m to 30 m. 7

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A waveguide as claimed in any preceding claim, wherein 9 the thickness of the second core layer is in the range 710 0.2 m to 30 11

A waveguide as claimed in Claim 24, wherein the width 13 of the waveguide core lies in the range 0.4 m to 60 14 m. 15

A waveguide as claimed in any of Claims 8 to 26, 27. 17

wherein the upper cladding layer and the lower cladding 18

layer comprise the same material. 19

A waveguide as claimed in any preceding claim, wherein 21 28. the refractive index of the substrate and the 22 refractive index of the upper cladding layer are 23 24 substantially equal.

An optical waveguide according to any of Claims 1 to 26 29. 28, wherein the first core layer includes at least 17% 27 wt germanium dopant. 28

A method of fabricating a waveguide comprising the 30 30. steps of: 31

providing a substrate; 32

forming a waveguide core on the substrate, the 1 waveguide core comprising a first core layer and a 2 3 second core layer; forming an upper cladding layer to embed the wavequide 4 5 core: wherein the formation of the first core layer includes 6 the doping of the first core layer with a dopant for 7 8 permitting the first core layer to exhibit a photosensitive response, and the formation of the 9 second core layer includes the doping of the second 7 10 core layer with a dopant for inducing amplification of 11 an optical signal transmitted through said wavequide 12 13 core. 14 A method according to Claim 30, wherein the dopant used 15 to permit the first core layer to exhibit a 16 17 photosensitive response is a germanium dopant. 18 A method according to Claim 31, wherein the first core 19 32. 20 layer is co-doped with a boron dopant. 21 22 A method as claimed in any of Claims 30 to 32, wherein 33. 23 the formation of the substrate includes the formation of an intermediate layer formed on said substrate. 24 25 26 A method as claimed in Claim 33, wherein the formation

30 35. A method as claimed in Claim 34, wherein the buffer layer is formed by thermally oxidizing the substrate.

32

27

28 29 buffer layer.

of the intermediate layer includes the formation of a

A method as claimed in Claim 34 or Claim 35, wherein 1 the formation of the intermediate layer further 2 includes the formation of a lower cladding layer formed 3 on said buffer layer. 4 5 A method as claimed in Claim 36, wherein the formation б 37. of the lower cladding layer includes doping said lower 7 cladding layer with a dopant. 8 9 ( ) 10 A method as claimed in Claim 37, wherein the dopant 38. includes dopant ions. 11 12 A method as claimed in any of Claims 30 to 38, wherein 13 39. the second core layer is formed on the first core layer 14 and wherein the first core layer is formed on the 15 substrate. 16 17 A method as claimed in any of Claims 30 to 39, wherein 18 40. the first core layer is formed on the second core layer 19 and said second core layer is formed on the substrate. 20 21 A method as claimed in Claim 39, wherein a further 22 first core layer is formed on the second core layer 23 such that the first core layer sandwiches the second 24 25 core layer. 26 A method as claimed in any of Claims 30 to 41, wherein 27 42. the steps of forming any one of the substrate, first 28 core layer, the second core layer, and the upper 29 cladding layer comprise the steps of: 30 depositing each layer; and 31 at least partially consolidating each layer. 32

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_		
2	43.	A method as claimed in Claim 42, wherein any one of the
3		substrate, the first core layer, the second core layer
4		and the upper cladding layer partially consolidated
5		after deposition is fully consolidated with the full

6 consolidation of any other of the first core layer, the

7 second core layer or the upper cladding layer.

9 44. A method as claimed in any of Claims 30 to 43, wherein 10 the formation of the substrate includes the doping of 11 the substrate with a dopant.

13 45. A method as claimed in any of Claims 30 to 44, wherein the dopant includes dopant ions.

16 46. A method as claimed in Claim 44 or Claim 45, wherein 17 the substrate dopant includes a mobile dopant.

19 47. A method as claimed in Claim 45 or Claim 46, wherein 20 said first core layer dopant ions include tin and/or 21 cerium and/or sodium.

- 23 48. A method as claimed in any of Claims 45 to 47, wherein 24 said second core layer dopant ions include a rare earth 25 and/or a heavy metal and/or compounds thereof.
- 27 49. A method as claimed in Claim 48, wherein said rare earth is Erbium and/or Neodymium.
- 30 50. A method as claimed in any of Claims 30 to 49, wherein 31 the concentration of the first core layer dopant is 32 selectively controlled during the formation of the

first core layer and the concentration of the second core layer dopant is selectively controlled during the formation of the second core layer so that the refractive index of the first core layer and the refractive index of the second core layer are substantially equal.

7

8 51. A method as claimed in Claim 50, wherein the
9 concentrations of the first core layer dopant and
10 second core layer dopant are controlled to give a
11 refractive index for the waveguide core which differs
12 from that of the substrate layer by at least 0.05%.

13

14 52. A method as claimed in any of Claims 34 to 51, wherein 15 said lower cladding layer and said buffer layer are 16 formed substantially in the same step.

17

18 53. A method as claimed in any of Claims 42 to 52, wherein 19 at least one of the substrate, the first core layer, 20 the second core layer, and the upper cladding layer is 21 deposited by a Flame Hydrolysis Deposition process 22 and/or Chemical Vapour Deposition process.

23

24 54. A method as claimed in Claim 53, wherein the Chemical
25 Vapour Deposition process is a Low Pressure Chemical
26 Vapour Deposition process or a Plasma Enhanced Chemical
27 Vapour Deposition process.

28

29 55. A method as claimed in any of Claims 42 to 54,
30 wherein the consolidation is by fusing using a Flame
31 Hydrolysis Deposition burner.

1 56. A method as claimed in any of Claims 42 to 55, wherein the consolidation is by fusing in a furnace.

3

4 57. A method as claimed in Claim 55 or Claim 56, wherein the step of fusing the lower cladding layer and the step of fusing the first core layer and/or the second core layer are performed simultaneously.

8

9 58. A method as claimed in any of Claims 30 to 57, wherein
10 the waveguide core is formed from the first core layer
11 and the second core layer using a dry etching technique
12 and/or a photolithographic technique and/or a
13 mechanical sawing process.

14

15 59. A method as claimed in Claim 58, wherein the dry
16 etching technique comprises a reactive ion etching
17 process and/or a plasma etching process and/or an ion
18 milling process.

19

20 60. A method as claimed in any of Claims 30 to 59, wherein 21 the waveguide core formed from the first core layer and 22 the second core layer is square or rectangular in 23 cross-section.

24

25 61. A method according to any of Claims 30 to 60, wherein 26 the first core layer is doped with at least 17%wt 27 germanium dopant.

28

29 62. A laser waveguide with multiple core layers for 30 transmitting an optical signal, the laser waveguide 31 comprising a waveguide as claimed in any of claims 1 to 32 29, the laser waveguide further comprising: at least one grating formed in said waveguide core.

2

3 63. A laser waveguide as claimed in Claim 62, wherein the laser waveguide further comprises at least one optical interference mirror.

6

7 64. A laser waveguide as claimed in Claim 63, wherein 8 the optical interference mirror is provided at the 9 input of the waveguide.

10

11 65. A laser waveguide as claimed in Claim 64, wherein the 12 interference mirror is butt-coupled to or directly 13 deposited at the input of the waveguide.

14

15 66. A laser waveguide as claimed in any of Claims 62 to 65, 16 wherein the laser waveguide includes two mirrors and a 17 grating.

18

19 67. A laser waveguide as claimed in any of Claims 62 to 65, 20 wherein the laser waveguide includes one mirror and two 21 gratings.

22

23 68. A laser waveguide as claimed in Claim 62, wherein the laser waveguide includes three gratings.

25

26 69. A laser waveguide as claimed in any of Claims 62 to 68, 27 wherein the grating formed is a Bragg grating.

28

29 70. A laser waveguide as claimed in any of Claims 62 to 69, 30 wherein said grating forms an output coupler for said 31 laser waveguide.

1 71. A laser waveguide as claimed in any of Claims 62 to 70
2 further comprising an optical interference mirror butt
3 coupled to or directly deposited at the output of the waveguide.

5

forming a waveguide according to a method as claimed in any of Claims 30 to 61, the method of fabricating the laser waveguide further including the steps of:

forming at least one grating in said waveguide core.

11

12 73. A method as claimed in Claim 72, further including the 13 step of attaching at least one optical interference 14 mirror to the waveguide.

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16 74. A method as claimed in Claim 73, wherein the optical interference mirror is attached to an input of the waveguide.

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20 75. A method as claimed in any of Claims 72 to 74, wherein
21 the grating is formed using a laser operating at a
22 wavelength in the range of 150 nm to 400 nm through a
23 phase mask deposited on top of said upper cladding
24 layer of the waveguide.

25

26 76. A method as claimed in Claim 75, wherein said mask is a quartz mask.

28

29 77. A method as claimed in any of Claims 72 to 74, wherein 30 the grating is formed using a using an interference 31 side writing technique.

29A

- 1 78. A method as claimed in any of Claims 72 to 74, wherein the grating is formed using a direct writing technique.
- 4 79. A method as claimed in any of Claims 72 to 78, wherein the grating formed is a Bragg grating.
- 7 80. A method as claimed in any of Claims 73 to 79, wherein 8 the optical interference mirror is butt-coupled to or 9 directly deposited at the input of the waveguide.
- 11 81. A method as claimed in any of Claims 72 to 79, further

  12 comprising the step of attaching a second optical

  13 interference mirror to the output of the waveguide.
- 15 82. A waveguide substantially as described herein and with 16 reference to Figs. 1A to 1C of the accompanying 17 drawings.
- 19 83. A laser waveguide substantially as described herein and with reference to Figs. 2A and 2B of the accompanying drawings.
- 23 84. A method of fabricating a waveguide with multiple core 24 layers substantially as described herein and with 25 reference to Figs. 1A to 1C of the accompanying 26 drawings.
- 28 85. A method of fabricating a laser waveguide with multiple
  29 core layers substantially as described herein and with
  30 reference to Figs. 2A and 2B of the accompanying
  31 drawings.

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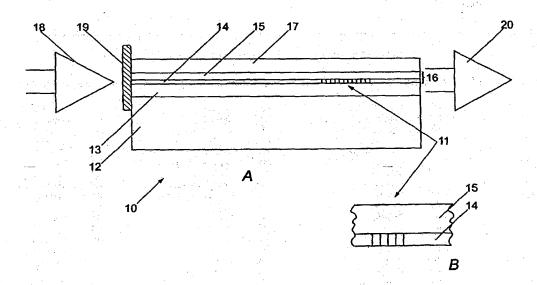
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(54) Title: OPTICAL WAVEGUIDE WITH MULTIPLE CORE LAYERS AND METHOD OF FABRICATION THEREOF



### (57) Abstract

An optical waveguide with multiple core layers for transmitting an optical signal comprises a substrate; an intermediate layer formed on said substrate; a waveguide core formed on said intermediate layer; and an upper cladding layer embedding said waveguide core. The waveguide core comprises a first core layer formed on said intermediate layer and a second core layer formed on said first core layer. The first core layer has photosensitive properties and the second core layer has optical gain properties.

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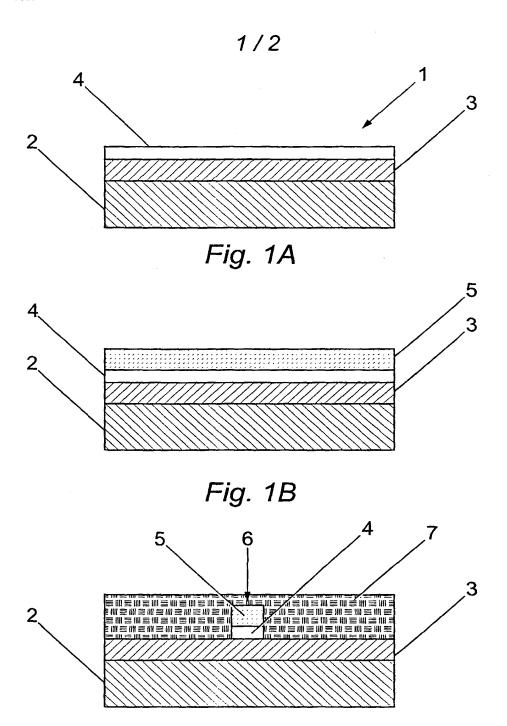
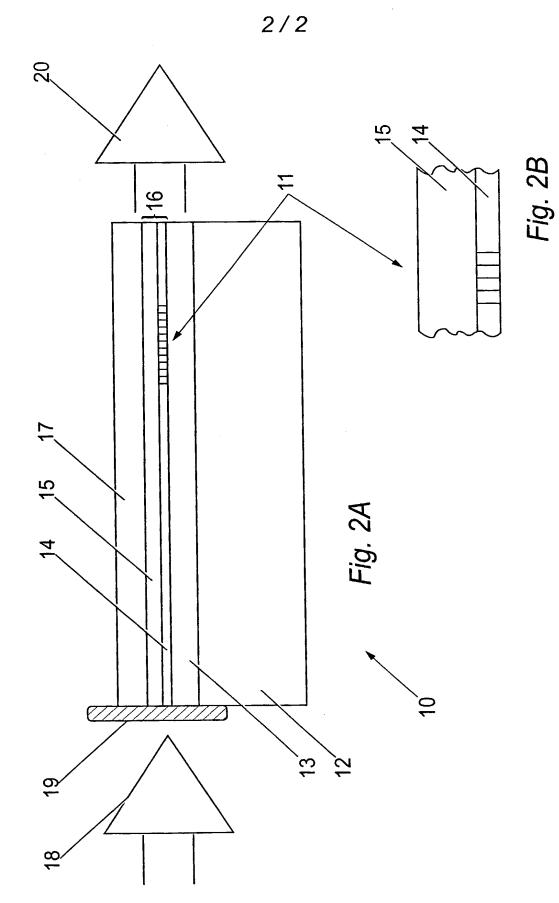


Fig. 1C

PCT/GB00/00323



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# DECLARATION, PETITION AND POWER OF ATTORNEY FOR PATENT APPLICATION

(Check one):

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ma

I hereby state that I have reviewed and understood the contents of the above-identified specification, including the claims, as amended by any amendment referred to above.

### PRIORITY CLAIM

(Check one):							
🗓 no such app	lications have be	en filed.					
🛭 such applica	ations have been	filed as follows					
States Code, §119(a) §365(a) of any PCT United States of Amforeign application f	(d) or §365(b) of international appli crica, listed below or patent or invent	I hereby claim foreign any foreign application cation which designate and have also identifi- for's certificate or any mon which priority is	on(s) for patent of at least one ed below, by ci FCT internation	or invente country of heaking th	or's comifica Nor than the to box, any	te or	
Prior Foreign	Country	Foreign Filing Date	Priority		ed Copy		
Application Number(2)		(4d/mm/yyyy)	Not Claimed	Yes	iched No	1	
9902477.0	CB	05 February 1999 (05.02.1999)			E		
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☐ Additional provi	sional application	numbers are listed on	a supplemental	priority s	heet attache	:d	
3) U.S./PCT PRIORITY CLAIM: I hereby claim the benefit under Title 35, United States Code, §120 of any United States application or §365(c) of any PCT international application designating the United States of America, listed below and, insofar as the subject matter of each of the claims of this application is not disclosed in the prior United States or PCT international application in the manner provided by the first paragraph of Title 35, United States Code, §112, I acknowledge the duty to disclose information which is known to me to be material to patentability as defined in Title 37, Code of Federal Regulations, §1.56 which became available between the filing date of the prior application and the national or PCT international filing date of this application.							
U.S. Parent Applicat Number	ion   PCT Parent		nt Filing Dave d/mm/yyyy)		Patent Num	nber	
				-			
Additional U.S. attached hereto.	or PCT internation	al application number	s are listed on a	suppleme	ental priority	y she	

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As a named inventor, I hereby appoint the following attorneys and/or agents to prosecute this application and transact all business in the Patent and Trademark Office connected therewith.

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Wherefore I petition that letters patent be granted to me for the invention or discovery described and claimed in the attached specification and claims, and hereby subscribe my name to said specification and claims and to the foregoing declaration, power of attorney, and this petition.

I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

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